

Title (en)

CLEANING COMPOSITION, METHOD FOR CLEANING A SILK SCREEN AND CLEANING DEVICE

Title (de)

REINIGUNGSMITTEL, VERFAHREN ZUR REINIGUNG VON SIEBDRUCKSCHABLONEN UND VORRICHTUNG ZUR REINIGUNG

Title (fr)

COMPOSITION NETTOYANTE, PROCEDE POUR NETTOYER UN ECRAN DE SERIGRAPHIE ET DISPOSITIF DE NETTOYAGE

Publication

EP 1222245 B1 20040804 (FR)

Application

EP 00969652 A 20001019

Priority

- FR 0002917 W 20001019
- FR 9913302 A 19991019
- FR 9913303 A 19991019
- FR 9914950 A 19991126

Abstract (en)

[origin: WO0129168A1] The invention concerns a cleaning composition comprising an aqueous solution containing between 0.05 to 5 wt. % of sodium metaperiodate and between 0.05 and 0.75 wt. % of sulphuric acid, and an aqueous solution of 0.5 to 90 wt. % of a mixture of dialkylesters and of 0.5 to 50 wt. % of a non-ionic surfactant. The method for cleaning a silk screen consists in exposing it to such a composition to eliminate ink, the masking product and the ghost image. The device for cleaning comprises a first section (4) wherein are a first ramp (26) of nozzles for spraying a cleaning composition on the screen (2) and a second ramp (32) of nozzles for spraying water under high pressure, and with which is associated a drain tank (20) for recovering the cleaning product and a reservoir (14) of cleaning product separate from the drain tank (20).

IPC 1-7

C11D 7/60; C11D 17/00; C11D 1/72; C11D 3/02; C11D 3/20; C11D 7/08; C11D 7/30; B41F 35/00

IPC 8 full level

B41N 3/06 (2006.01); **B08B 1/04** (2006.01); **B08B 3/02** (2006.01); **B08B 3/08** (2006.01); **B41F 35/00** (2006.01); **C11D 1/72** (2006.01); **C11D 3/02** (2006.01); **C11D 3/20** (2006.01); **C11D 3/395** (2006.01); **C11D 7/08** (2006.01); **C11D 7/30** (2006.01); **C11D 7/56** (2006.01); **C11D 7/60** (2006.01); **C11D 11/00** (2006.01); **C11D 17/00** (2006.01)

CPC (source: EP US)

B08B 3/022 (2013.01 - EP US); **B41F 35/005** (2013.01 - EP US); **C11D 1/72** (2013.01 - EP US); **C11D 3/042** (2013.01 - EP US); **C11D 3/2093** (2013.01 - EP US); **C11D 3/3956** (2013.01 - EP US); **C11D 7/08** (2013.01 - EP US); **C11D 17/0017** (2013.01 - EP US); **B41P 2235/31** (2013.01 - EP US); **B41P 2235/50** (2013.01 - EP US); **C11D 2111/20** (2024.01 - EP US)

Citation (examination)

DE 2914453 C2 19831013

Cited by

CN114247680A; CN106626759A; WO2006037333A3

Designated contracting state (EPC)

AT BE CH CY DE DK ES FI FR GB GR IE IT LI LU MC NL PT SE

DOCDB simple family (publication)

WO 0129168 A1 20010426; AT E272704 T1 20040815; AU 7931700 A 20010430; CA 2355703 A1 20010426; CA 2355703 C 20051018; DE 60012767 D1 20040909; DE 60012767 T2 20050825; EP 1222245 A1 20020717; EP 1222245 B1 20040804; ES 2225236 T3 20050316; JP 2003512203 A 20030402; US 6579381 B1 20030617

DOCDB simple family (application)

FR 0002917 W 20001019; AT 00969652 T 20001019; AU 7931700 A 20001019; CA 2355703 A 20001019; DE 60012767 T 20001019; EP 00969652 A 20001019; ES 00969652 T 20001019; JP 2001531955 A 20001019; US 86832101 A 20010702